

Notice of References Cited	Application/Control No. 10/643,680	Applicant(s)/Patent Under Reexamination KRAUS ET AL.	
	Examiner Eric B. Fuller	Art Unit 1762	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,554,501	09-1996	Coassin et al.	435/6
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
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	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Baker et al., Highly Conformal Thin LFilms of Tungsten Nitride Prepared by Atomic Layer Deposition from a Novel Precursor, June 20, 2003, Chem. Mater. 2003, 15, 2969-2976.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.